Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

- 1.-8. (canceled)
- 9. (currently amended) A process for fabrication of a toothed belt, comprising: forming an elongate belt body of an elastomeric material, the belt having a first, planar side and a second side opposite the first side;

forming teeth along the second side;

coating the teeth with a fabric of a polymeric material;

treating the fabric with a liquid solution of RFL to impregnate fibres of the fabric; coating the treated fabric with a resistant layer comprising a fluorinated plastomer and an elastomeric material, the fluorinated plastomer being present in the resistant layer in an amount between 101 and 150 parts by weight of an amount of the elastomeric material and containing more than 50% of particles of a size smaller than 10um; and

directly adhering the resistant layer to the fabric coated over the teeth, wherein the resistant layer is applied directly to the fabric via spreading <u>a weight of the fluorinated plastomer and elastomeric material between 50 and 80 g/m² to produce a uniform thickness resistant layer on the treated fabric.</u>

- 10. (currently amended) A process according to claim [[8]] 9 in which forming the elongate belt body includes embedding a plurality of longitudinal filiform resistant inserts or cords in the elastomeric material.
- 11. (currently amended) The toothed belt A process according to Claim [[1]]9, characterized in that said elastomeric material comprises HNBR.
- 12. 19. (canceled)
- 20. (new) A process according to Claim 9, characterized in that said fluorinated plastomer is polytetrafluoroethylene.

- 21. (new) A process according to Claim 20, characterized in that said elastomeric material comprises HNBR.
- 22. (new) A process according to Claim 21, characterized in that said elastomeric material comprises HNBR modified with a zinc salt of polymethacrylic acid.
- 23. (new) A process according to Claim 9, characterized in that the resistant layer thickness is from 30 and 50 micrometers.